JAN 0 3 2005 6

E		Application Number	09/677805	
MARYER	FACSIMILE TRANSMITTAL FORM	Filing Date	October 2, 2000	
		First Named Inventor	Bedingham, William	
FORM		Art Unit	1743	
		Exeminer Name	Brian R. Gordon	
Fax: 70	03-746-4000	Attorney Docket Number	55943US003	
Total Nun	nber of Pages in This Submission	: 6 including fax cover shee	it	
Date: January 3, 2005		Attorney for Applicant: Christopher D. Gram		

		ENCLOSURES (check all that apply)	
□ Fe ⊠	ee Transmittal Form Issue Fee Transmittal Amendment Transmittal	☐ Petition	Appeal Communication to Board of Appeals and Interferences
Ar	mendment/Reply] After Final] Affidavits/Declaration(s)	Petition to Convert a Provisional Application	Appeal Communication to Technology Center (Appeal Notice, Brief, Reply Brief)
□ E	xtension of Time Request	Power of Attorney, Revocation	Proprietary Information
	xpress Abandonment equest	Change of Correspondence Address	Status Letter
	formation Disclosure tatement	☐ Terminal Disclalmer	○ Other Enclosures: Comments on Statement of
□ R In	esponse to Missing Parts/	Request for Refund	Reasons for Allowance
	Response to Missing Parts under 37 CFR § 1,52 or 1.53	Request for Continued Examination (RCE) Transmittal	
□ D	rawings	After Allowance Communication to Technology Center	
		REMARKS:	

THE INFORMATION CONTAINED IN THIS FACSIMILE TRANSMISSION MAY CONTAIN CONFIDENTIAL OR LEGALLY PRIVILEGED INFORMATION INTENDED ONLY FOR THE PERSON OR ENTITY NAMED BELOW.

If you are not the intended recipient, please do not read, use, disclose, distribute or copy this transmission.

If this transmission was received in error, please immediately notify me by telephone directly at (651) 733-1507 or 651-733-1500, and we will arrange for its return at no cost to you.



Patent Case No.: 55943US003

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

First Named Inventor:

BEDINGHAM, WILLIAM

Application No.:

09/677805

ID:3M 220-11-01

Group Art Unit: 1743

Filed:

October 2, 2000

Examiner:

Brian R. Gordon

Title:

SAMPLE PROCESSING APPARATUS, METHODS AND

SYSTEMS

COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

CERTIFICATE OF MAILING OR TRANSMISSION [3	CFR § 1.8	3(a)
---	-----------	------

I hereby certify that this correspondence is being:

deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patenta, P.O. Box 1450, Alexandria, VA 22313-1450.

Iransmitted by facsimile on the date shown below to the United States Patent and Trademark Office at (703) 872-9306.

Dear Sir:

Applicants thank the Examiner for indicating that claims 6-8, 13, and 16-49 are allowable and have noted the Examiner's reasons for finding the claims allowable. Applicants, however, respectfully make the following comments with respect to the Examiner's statements regarding allowability of the claims. Applicants' comments do not affect allowability of claims 6-8, 13, and 16-49 and are presented to indicate that the Examiner's stated reasons for allowance should not be construed as limiting all of the allowed claims.

Applicants agree with the Examiner that the prior art does not teach or fairly suggest an apparatus for processing sample materials, the apparatus comprising: a platform comprising an upper surface and a lower surface; a plurality of stationary fluid chambers opening at the upper surface of the platform; retention structure occupying a portion of the upper surface of the platform, wherein the retention structure is capable of retaining a rotating multi-chambered processing device proximate the upper surface of the platform and wherein at least some of the plurality of stationary fluid chambers further comprise filter material, as recited in claim 6. Applicants respectfully point out, however, that neither claim 6 nor any other independent claim

4

recited herein, recites that the filter material is for filtering the sample material prior to the sample being placed in the multi-chambered processing device.

Additionally, Applicants point out that the present invention includes alternative embodiments of an apparatus for processing sample materials. In particular, the present invention also includes an apparatus for processing sample materials, the apparatus comprising: a platform comprising an upper surface and a lower surface; a plurality of stationary fluid chambers opening at the upper surface of the platform, wherein the plurality of stationary fluid chambers are arranged in a rectilinear array on the upper surface of the platform; retention structure occupying a portion of the upper surface of the platform; and a processing device located within the retention structure proximate the upper surface of the platform, the processing device comprising a plurality of process chambers, wherein the processing device is capable of being rotated within the retention structure to move the plurality process chambers, and wherein at least one of the process chambers on the processing device is positioned at a transfer site proximate the upper surface of the platform, wherein the location of the transfer site is fixed relative to the stationary fluid chambers and further comprising complementary registration structure on the platform and the processing device, the complementary registration structure aligning the at least one process chamber at the location defined by the rectilinear array of the stationary fluid chambers when the processing device is stationary, as recited in claim 13.

Applicants further point out that the present invention also includes the following embodiments, as recited in claim 16 and claim 20: an apparatus for processing sample materials, the apparatus comprising: a platform comprising an upper surface and a lower surface; a plurality of stationary fluid chambers opening at the upper surface of the platform wherein at least some of the plurality of stationary fluid chambers further comprise filter material; retention structure occupying a portion of the upper surface of the platform; and a processing device located within the retention structure proximate the upper surface of the platform, the processing device comprising a plurality of process chambers, wherein the processing device is capable of being rotated within the retention structure to move the plurality process chambers (claim 16), and an apparatus for processing sample materials, the apparatus comprising: a platform comprising an upper surface and a lower surface; a plurality of stationary fluid chambers opening at the upper surface of the platform; retention structure occupying a portion of the upper surface of the platform; retention structure occupying a portion of the upper surface of the platform; and a processing device located within the retention structure proximate the upper

5

Application No.: 09/677805

Case No.: 55943US003

surface of the platform, the processing device comprising a plurality of process chambers, wherein the processing device is capable of being rotated within the retention structure to move the plurality process chambers and wherein the processing device is captive within the retention structure on the platform (claim 20).

The present invention additionally includes methods and systems for processing sample materials. Specifically, the present invention includes a method of processing sample material, the method comprising: providing a platform comprising an upper surface and a lower surface, a plurality of stationary fluid chambers opening at the upper surface of the platform, and retention structure occupying a portion of the upper surface of the platform; providing a processing device in the retention structure proximate the upper surface of the platform, the processing device comprising a plurality of process chambers; providing sample material in a plurality of the plurality of process chambers on the processing device; delivering energy to the process chambers containing sample material to raise the temperature of the sample materials in the process chambers; and rotating the processing device about an axis of rotation within the retention structure while delivering the energy, wherein the temperature of the sample materials in the process chambers is controlled as the processing device rotates to process the sample materials, as recited in claim 21.

The present invention further includes a method of processing sample material, the method comprising: providing a platform comprising an upper surface and a lower surface, a plurality of stationary fluid chambers opening at the upper surface of the platform, and retention structure occupying a portion of the upper surface of the platform, wherein the plurality of stationary fluid chambers are arranged in a rectilinear array on the upper surface of the platform; placing a processing device in the retention structure proximate the upper surface of the platform, the processing device comprising a plurality of process chambers; positioning at least one of the process chambers on the processing device at a transfer site proximate the upper surface of the platform, wherein the location of the transfer site is fixed relative to the stationary fluid chambers; loading sample material in a plurality of the plurality of process chambers on the processing device, wherein the process chambers are loaded while positioned at the transfer site; rotating the processing device about an axis of rotation within the retention structure on a spindle extending through a spindle opening formed through the upper and lower surfaces of the platform; delivering energy to at least some of the plurality of process chambers containing

6

Case No.: 55943US003

Application No.: 09/677805

sample material while rotating the processing device to control the temperature of the sample materials in the process chambers, whereby the sample materials are processed; and transferring the sample materials from the process chambers on the processing device to the plurality of stationary fluid chambers on the platform after processing the sample materials; where the sample materials in the process chambers are transferred while the process chambers are located at the transfer site, as recited in claim 35.

The present invention also includes a system for processing sample material, the system comprising: a workspace comprising a processing station; at least one platform located within the workspace, each platform comprising an upper surface and a lower surface, a plurality of stationary fluid chambers opening at the upper surface of the platform, and retention structure occupying a portion of the upper surface of the platform; at least one processing device located within the workspace, each processing device comprising a plurality of process chambers, wherein rotation of the processing device within the retention structure on the platform moves the plurality process chambers in a circular pattern; a spindle located at the processing station; and a transfer device operative within the workspace, the transfer device capable of transferring sample material from the processing station to another location within the workspace, as recited in claim 44.

Applicants respectfully request that the Examiner contact the undersigned attorney with any questions regarding these comments.

It is believed that no fee is due; however, in the event a fee is required, please charge the fee to Deposit Account No. 13-3723.

Respectfully submitted,

Christopher D. Gram, Reg. No.: 43,643

Telephone No.: (651) 733-1507

Office of Intellectual Property Counsel 3M Innovative Properties Company

1/8/2005

Facsimile No.: 651-736-3833